AMENDMENTS TO THE CLAIMS:

Please amend Claims 1-3, 9-11, 16, 21, and 29 as follows. In accordance with the Revised Amendment Format, the status of all claims are presented below.

1. (Currently Amended) A method for manufacturing an electron-emitting device, comprising:

a step for forming a <u>solid-state insulating</u> polymer film <u>including a</u>

<u>carbon atomic bond</u> between a pair of electrodes formed on a substrate;

a step for giving conductivity to said polymer film by heating said polymer film to change said polymer film into an electro-conductive film; and

a step for providing <u>a</u> potential difference between said pair of electrodes <u>to energize electrically the electro-conductive film</u>.

- 2. (Currently Amended) A method according to claim 1, wherein the step for giving conductivity to said polymer film by heating includes a step for illuminating an electron beam onto at least a part of said polymer film.
- 3. (Currently Amended) A method according to claim 1, wherein the step for giving conductivity to said polymer film by heating includes a step for illuminating light onto at least a part of said polymer film.
- 4. (Original) A method according to claim 3, wherein the light is light emitted from a xenon lamp as a light source.





- 5. (Original) A method according to claim 3, wherein the light is light emitted from a halogen lamp as a light source.
- 6. (Original) A method according to claim 3, wherein the light is a laser beam.
- 7. (Original) A method according to claim 1, wherein said polymer film is an aromatic polymer film.
- 8. (Original) A method according to claim 1, wherein the step for forming a polymer film utilizes an ink jet system.
- 9. (Currently Amended) A method for manufacturing an electron-emitting device, comprising:

a step for forming a <u>solid state</u> polymer film <u>including a carbon</u> atomic bond between a pair of electrodes formed on a substrate;

a step for reducing electrical resistance of said polymer film by heating said polymer film to change the polymer film into an electro-conductive film having an electrical resistance lower than that of the polymer film; and

a step for providing <u>a</u> potential difference between said pair of electrodes <u>to energize electrically said electro-conductive film</u>.

10. (Currently Amended) A method according to claim 9, wherein the step for reducing electrical resistance of said polymer film by heating said polymer film includes a step for illuminating an electron beam onto at least a part of said polymer film.

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- 11. (Currently Amended) A method according to claim 9, wherein the step for reducing electrical resistance of said polymer film by heating said polymer film includes a step for illuminating light onto at least a part of said polymer film.
- 12. (Original) A method according to claim 11, wherein the light is light emitted from a xenon lamp as a light source.
- 13. (Original) A method according to claim 11, wherein the light is light emitted from a halogen lamp as a light source.
- 14. (Original) A method according to claim 11, wherein the light is a laser beam.
- 15. (Original) A method according to claim 9, wherein the step for forming a polymer film utilizes an ink jet system.
- 16. (Currently Amended) A method for manufacturing an electron-emitting device, comprising:

a step for forming a polymer film <u>including a carbon atomic bond</u> between a pair of electrodes formed on a substrate;

a step for illuminating an electron beam onto at least a part of said polymer film; and

a step for providing <u>a</u> potential difference between said pair of electrodes.

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17. (Original) A method according to claim 16, wherein the step for illuminating the electron beam onto said polymer film includes a step for giving conductivity to at least a part of said polymer film.

18. (Original) A method according to claim 16, wherein the step for illuminating the electron beam onto said polymer film includes a step for reducing electrical resistance of said polymer film.



and

19. (Original) A method according to claim 16, wherein said polymer film is an aromatic polymer film.

20. (Original) A method according to claim 16, wherein the step for forming a polymer film utilizes an ink jet system.

21. (Currently Amended) A method for manufacturing an electron-emitting device, comprising:

a step for forming a polymer film <u>including a carbon atomic bond</u> between a pair of electrodes formed on a substrate;

a step for illuminating light onto at least a part of said polymer film;

a step for providing <u>a</u> potential difference between said pair of electrodes.

- 22. (Original) A method according to claim 21, wherein the step for illuminating light onto said polymer film includes a step for giving conductivity to at least a part of said polymer film.
- 23. (Original) A method according to claim 21, wherein the step for illuminating light onto said polymer film includes a step for reducing electrical resistance of said polymer film.
- 24. (Original) A method according to claim 23, wherein the light is light emitted from a xenon lamp as a light source.
- 25. (Original) A method according to claim 23, wherein the light is light emitted from a halogen lamp as a light source.
- 26. (Original) A method according to claim 23, wherein the light is a laser beam.
- 27. (Original) A method according to claim 21, wherein said polymer film is an aromatic polymer film.
- 28. (Original) A method according to claim 21, wherein the step for forming a polymer film utilizes an ink jet system.
- 29. (Currently Amended) A method for manufacturing an electron source having a plurality of electron-emitting devices, wherein:

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each said electron-emitting device is manufactured in accordance with any one of methods the method according to any one of claims 1 to 28.

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30. (Original) A method for manufacturing an image-forming apparatus having an electron source including a plurality of electron-emitting devices, and an image-forming member for forming an image by illumination of electron emitted from said electron source, wherein:

said electron source is manufactured by a method according to claim 29.

